

AME P5000 Chamber B



Facts

The AME P5000 is a multi-chamber tool set up for a variety of processes

- Chamber B - PECVD TEOS for contamination threat substrates - [we are currently working on configuring this chamber](#)
 - III-V / Au / Cu coated wafers may be processing in this chamber
- Other Chambers
 - AME P5000 Chamber A - PECVD of TEOS Silicon Dioxide
 - AME P5000 Chamber C - RIE of Silicon Dioxide

Personnel

- Tool Engineer - John Nash
- Process Engineer - Sean O'Brien

Manuals & Users

- P5000 Manual
- P5000 Certification Checklist